High-Precision Glass-on-Glass Printing via Laser-Induced Forward Transfer of Solid State SiO$_x$: Fabrication Technique and Optical Applications

Nastaran Bakhtiari, Jürgen Ihlemann**

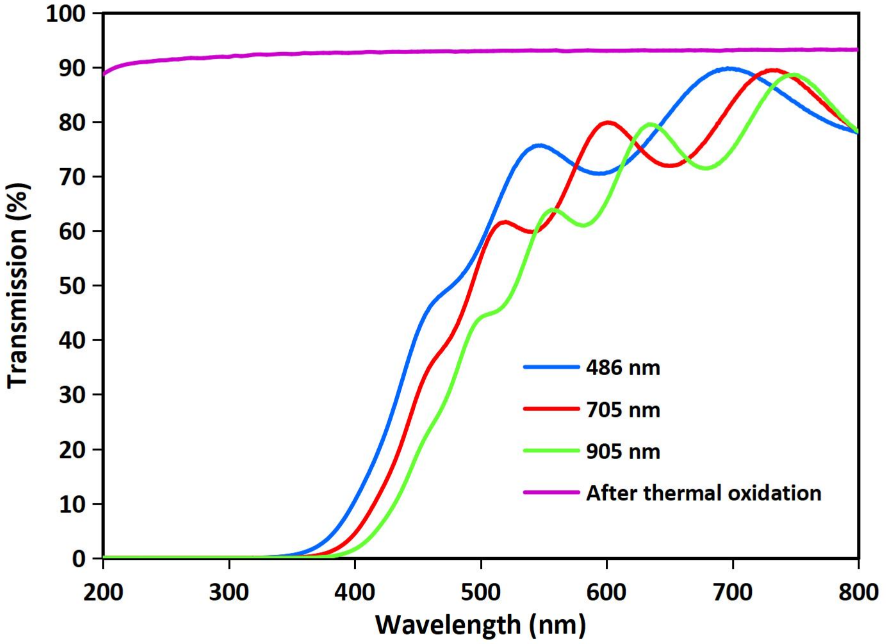

Figure S1. Transmission spectra of SiO$_x$ films with thicknesses of 486 nm, 705 nm, and 905 nm on fused silica, including a 705 nm sample after thermal oxidation (1000 °C, 48 h in air).

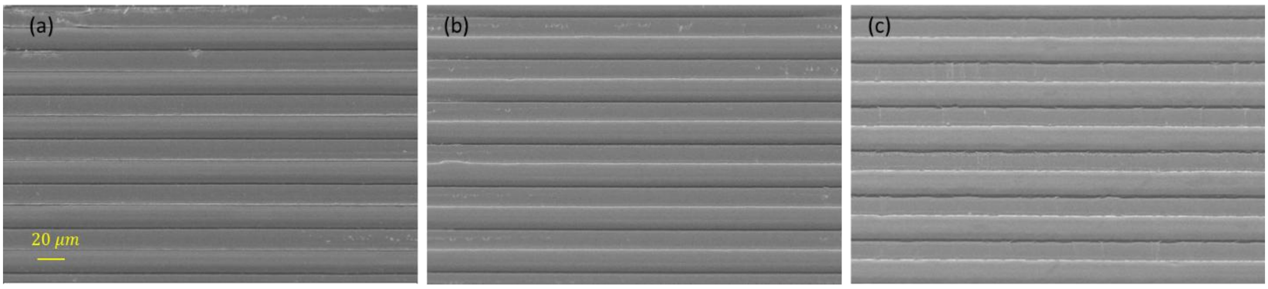

Figure S2. SEM images of printed SiO$_x$ strips on BK7 substrates with layer thicknesses from left to right: 486 nm, 705 nm, and 950 nm.